제20회 한국반도체학술대회

2013년 2월 4일(월)~6일(수) / 웰리힐리파크 (구, 성우리조트)

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A. Interconnect & Package 분과

Room G

국실 (본관, 5층)

2013년 2월 5일(화) 10:55-12:10 [TG2-A] 배선용 박막 증착 기술

좌장: 이원준(세종대학교), 이태윤(연세대학교)

TG2-A-1 10:55-11:10 Atomic Layer Deposition of Ruthenium (Ru) Thin Films using a Novel

Zero-Valent Ru Metallorganic Precursor as a Seed Layer for Copper Metallizations

Seungmin Yeo¹, Seung-Joon Lee¹, Taehoon Cheon², Jun-Young Kim³, Jung Woo Park³, and Soo-Hyun Kim¹

¹School of Materials Science and Engineering, Yeungnam University, ²Center for Core Research Facilities, Daegu Gyeongbuk Institute of Science & Technology, ³Thin Film Material Team, Hansol Chemical Co., Ltd.

TG2-A-2 11:10-11:25 Atomic Layer Deposition of Ruthenium-Oxide Thin Films by using Novel Zero-Valent Ru Metallorganic Precursors and Oxygen Molecules

Ji-Yoon Park¹, Seungmin Yeo¹, Soo-Hyun Kim¹, Taehoon Cheon², Mingyu

Kim³, Hyungjun Kim³ and Tae-Eun Hong⁴ ¹School of Materials Science and Engineering, Yeungnam University,

²Center for Core Research Facilities, Daegu Gyeongbuk Institute of Science & Technology, ³School of Electrical and Electronic Engineering, Yonsei University, ⁴Busan Center, Korea Basic Science Institute

TG2-A-3 11:25-11:40 Effect of Laser Energy on the Deposition of Patterned Tungsten (W)

Thin Films using Laser Chemical Vapor Deposition (LCVD) at **Atmospheric Pressure**

Kyunghoon Jeong¹, Injae Byun², Dong-Gil Kim², Do-Soon Jung², and Jaegab Lee¹

¹School of Advanced Materials Engineering, Kookmin University, ²Charm Engineering Co.

Controlled Growth of TiC and TiN Thin Film by Atomic Layer TG2-A-4 11:40-11:55

Deposition and Application to the Diffusion Barrier for Cu Metallization

Sang-Kyung Choi¹, Soo-Hyun Kim¹, and Taehoon Cheon² ¹School of Materials Science and Engineering, Yeungnam University, ²Center for Core Research Facilities, Daegu Gyeongbuk Institute of Science & Technology